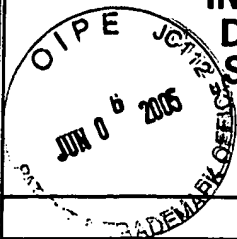


# INFORMATION DISCLOSURE STATEMENT



SHEET 1 OF 1

Complete if known

Application Number: 10/076,858

Filing Date: February 14, 2002

First Named Inventor: Steinberg

Group Art Unit: 1775

Examiner Name: Stephen J. Stein

Attorney Docket Number: R&H 03-19

## UNITED STATES PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	PATENT NUMBER	ISSUE DATE MM-DD-YYYY	FIRST NAMED INVENTOR
		4810557	03/07/1989	Blonder
		4837129	06/06/1989	Frisch et al.
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		US 2003/0021572	01/30/2003	Steinberg

## FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	DOCUMENT NUMBER	COUNTRY OR REGION	DATE OF PUBLICATION MM-DD-YYYY	FIRST NAMED INVENTOR OR APPLICANT

## OTHER PRIOR ART - NON-PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	Include name of the author (in Capital Letters), title of the article (when appropriate), title of the item(book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published
		Nijdam, et al. "Etching of silicon in alkaline solutions: a critical look at the {111} minimum," MESA
		Oosterbroek, et al. "New design methodologies in <111> oriented silicon wafers," MESA
		Suchtelen, et al. "Simulation of Anisotropic Wet-Chemical Etching Using a Physical Model," MESA

EXAMINER'S SIGNATURE	DATE CONSIDERED

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP §609. Draw a line through citation if citation not in conformance and reference not considered. Include a copy of this form with next communication to applicant.